

SU-8 2025 – run sheet

MicroChem

nanyte.com/photoresists/su-8-2025 · last updated 2026-07-26

Thickness: 21.7–79.2 μm

Exposure dose – dose by film thickness

Film thickness	Dose
25–40 μm	150–160 mJ/cm^2
45–80 μm	150–215 mJ/cm^2
85–110 μm	215–240 mJ/cm^2
115–150 μm	240–260 mJ/cm^2
160–225 μm	260–350 mJ/cm^2

Develop: Developer SU-8 Developer (MicroChem) · Rinse IPA ·
Method immersion

Hardbake: 150–250 $^{\circ}\text{C}$ · 5–30 min